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GE Hitachi Nuclear Energy

Proprietary Notice

This letter transmits proprietary information in accordance with 10CFR2.390. Upon the removal of Enclosure 1, the balance of the letter may be considered non-proprietary.

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MFN 11-028
February 23, 2011

U.S. Nuclear Regulatory Commission
Document Control Desk
Washington, D.C. 20555-0001

Subject: NEDE-33633P and NEDO-33633, “Licensing Topical Report GEH Methodology for Implementing TSTF-493 Revision 4”

GE-Hitachi Nuclear Energy Americas LLC (GEH) is submitting NEDE-33633P, “Licensing Topical Report GEH Methodology for Implementing TSTF-493 Revision 4,” Revision 0, February 2011, for review and approval under the NRC’s licensing topical report (LTR) program for referencing in licensing actions. This LTR describes the methodology developed by GEH for calculating as-found and as-left tolerances for setpoints in the BWR plant Technical Specifications that comply with the guidance in TSTF-493 Revision 4. This LTR is a normal topical report that is applicable to all BWR/2-6 Licensees. GEH requests that the NRC review be completed within 12 months following the receipt of this report. Because the approval of this LTR will assist NRC in the timely review of Licensees’ TSTF-493 applications, GEH is requesting an expedited review.

Please note that Enclosure 1 contains proprietary information of the type that GEH maintains in confidence and withholds from public disclosure. The information has been handled and classified as proprietary to GEH as indicated in its affidavit, also included in the report. The affidavit contained in Enclosure 3 identifies that the information contained in Enclosure 1 has been handled and classified as proprietary to GEH. GEH hereby requests that the information in Enclosure 1 be withheld from public disclosure in accordance with the provisions of 10 CFR 2.390 and 9.17.

Enclosure 2 is the non-proprietary version of Enclosure 1.

If you have any questions about the information provided here, please contact me at (910) 819-5744.

Sincerely,



Edward D. Schrull, PE
Vice President, Services Licensing
Regulatory Affairs
GE Hitachi Nuclear Energy

No commitments are made in this letter or its enclosures.

Enclosures:

1. NEDE-33633P, Revision 0, "Licensing Topical Report GEH Methodology for Implementing TSTF-493 Revision 4," February 2011 – GEH Proprietary Information – Class III (Confidential)
2. NEDO-33633, Revision 0, "Licensing Topical Report GEH Methodology for Implementing TSTF-493 Revision 4," February 2011 – Non-Proprietary Information – Class I (Public)
3. Affidavit, dated February 23, 2011

cc: SS Philpott, NRC
D Rahn, NRC
JG Head, GEH Wilmington
PL Campbell, GEH Washington
ED Schrull, GEH/Wilmington
eDRF Section 0000-0127-6662 R1

Document Components:

001 MFN 11-028 Cover Letter.pdf
002 MFN 11-028 Enclosure 1 Proprietary.pdf
003 MFN 11-028 Enclosure 2 Non-Proprietary.pdf
004 MFN 11-028 Enclosure 3 Affidavit.pdf